## IAP20 Rec'd FOT/TTO 15 FEB 2006

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**PATENT** 

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Yasuo KOBAYASHI, et al.

International Application No.: PCT/JP2004/011595

International Filing Date: August 12, 2004

U.S. Serial No.: To Be Assigned

Group Art Unit: To Be Assigned

Filed: : Herewith

Examiner: To Be Assigned

For: SEMICONDUCTOR DEVICE, MANUFACTURING METHOD OF SEMICONDUCTOR DEVICE, AND GAS FOR PLASMA CVD PROCESS

## PRELIMINARY AMENDMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Prior to or concurrent with calculation of the filing fees, please amend this application as follows.